# Monthly LabAdviser update: 17/1 2013

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| Updated Subject  | Contributer | Link to the update pages |
| **New e-mail template for e-beam requests****E-mail request for metal wishes now also for physimeca** | Tine Greibe@ danchip Jesper Hanberg @ danchip | [http://labadviser.danchip.dtu.dk/index.php/Template:DanchipInfo](http://labadviser.danchip.dtu.dk/index.php/Template%3ADanchipInfo) |
| E-beam | Tine Greibe@ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/E-beam_lithography> |
| **DRIE-pegasus**Sloped sidewalls | Jonas M. Lindhard @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/DRIE-Pegasus/slopedsidewalls> |
| **Wafer info** | Yvonne @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Wafer_Information> |
| **Info on some standard masks used at Danchip for QC and development** | Jonas M. Lindhard @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Photolithography/masks/travka><http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Photolithography/masks/travka/fields/Aline> |
| **SEM’s**Improved overview page | Jonas M. Lindhard @ danchip | [http://labadviser.danchip.dtu.dk/index.php/Specific\_Process\_Knowledge/Characterization/SEM:\_Scanning\_Electron\_Microscopy](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/SEM%3A_Scanning_Electron_Microscopy) |
| **AOE**SiO2 etch with Si mask | Berit G. Herstrøm @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Etching_of_Silicon_Oxide/SiO2_etch_using_AOE> |
| **Dry etcher’s**New comparison page | Jonas M. Lindhard @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/ICP> |
| **ICP metal etcher** | Jonas M. Lindhard @ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/ICP_Metal_Etcher> |